

## 1 Supporting Information

### 2 High speed electrically switching reflective structural color display with large 3 color gamut

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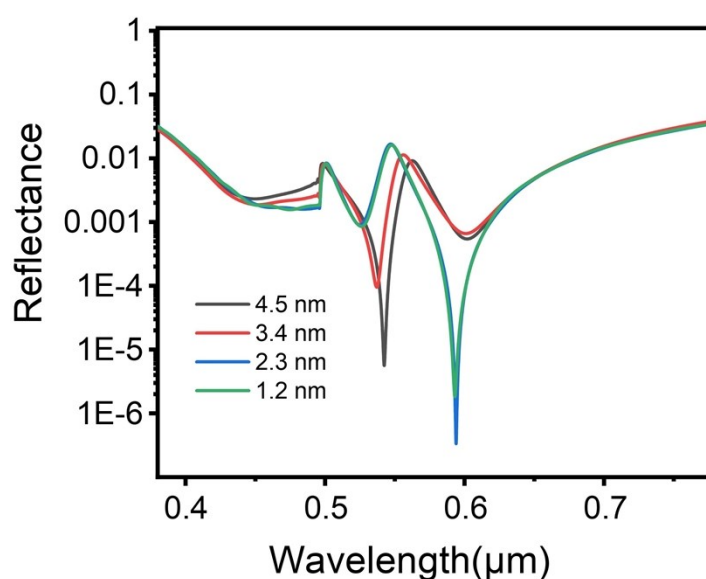
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### 16 1 Mesh grids setting and convergence test in FDTD simulations

17 Non-uniform mesh settings were used in the FDTD simulations. An overriding mesh  
18 with minimum grid size  $dx = dy = 1.2$  nm was added in the grating, ITO and  $Al_2O_3$  film  
19 region. The minimum grid size of 1.2 nm was determined by the convergence test in

20 Fig. S1.



21

22 **Fig. S1.** The reflectance spectra for Green pixel at color-off state with different

23 minimum grid size.

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25 **2 The influence of  $ITO_{active}$  layer thicknesses on the anti-reflection at color-off**  
26 **state**

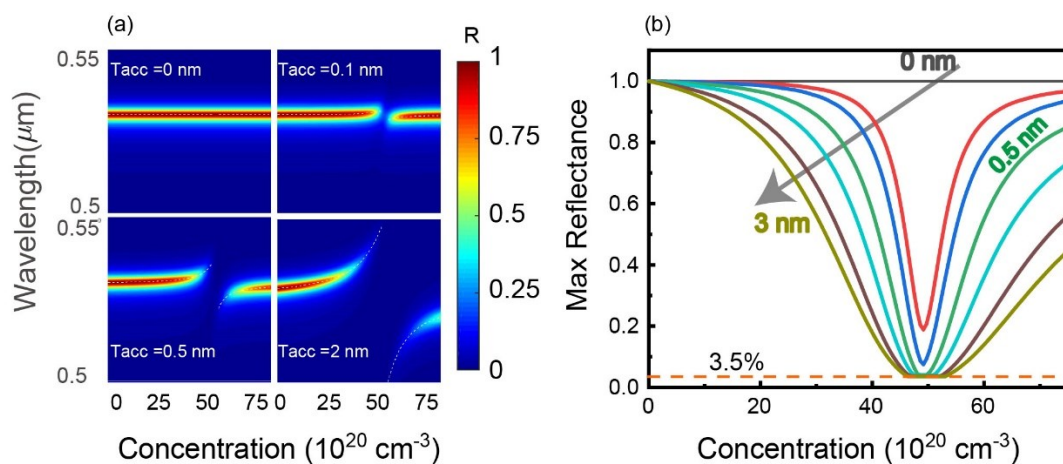
27 Different  $ITO_{active}$  layer thicknesses were used at different wavelength range in the  
28 references, like  $5\pm 1$  nm at  $0.5 \mu\text{m} \sim 0.8 \mu\text{m}$ ,<sup>1</sup> 1.5 nm at  $\sim 4 \mu\text{m}$ ,<sup>2</sup> 0.9 nm at  $1.55 \mu\text{m}$ .<sup>3</sup>

29 We evaluated the influence of  $ITO_{active}$  layer thicknesses on the anti-reflection at the  
30 green pixel's color-off state through RCWA method in Fig. S2.  $T_{acc} = 0.5$  nm was thick  
31 enough to suppress reflectance below 3.5% and guaranteed a good anti-reflection effect.

32 Larger  $T_{acc}$  values gave wider carrier-concentration work windows with sufficient low  
33 reflectance. And in visible region,  $T_{acc}$  can be 5 nm according to reference.<sup>1</sup> So the  
34 compromised  $T_{acc}$  value of 2.5 nm could ensure the satisfied modulation effect with  
35 reduced practical control requirement and was used in the main text.

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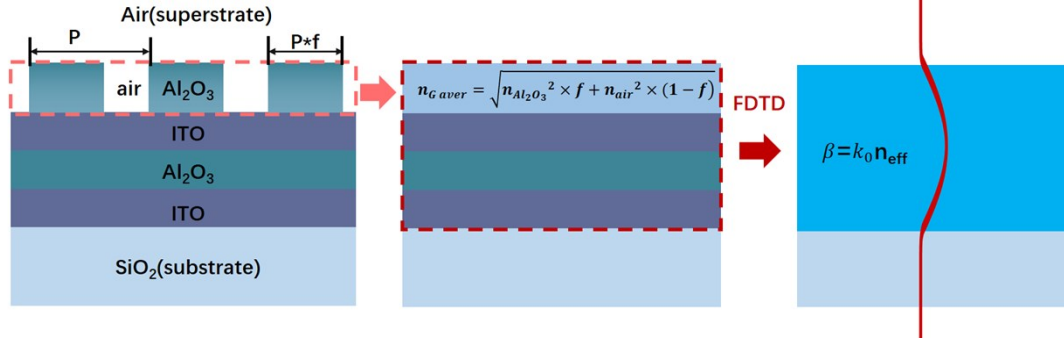


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39 **Fig. S2** (a) The reflectance spectra vs. carrier concentration contour plot for different

40  $T_{acc}$ . (b) The maximum reflectance vs. electron concentration for different  $T_{acc}$ .

41 **3 Extraction of the effective index  $n_{eff}$**



42

43 **Fig. S3** Extraction of the effective index  $n_{eff}$ .

44 The GMR grating has a sub-wavelength period. Thus the 0 order diffraction is the main

45 channel.<sup>4</sup> We extracted the effective index of the GMR grating as below. The  $Al_2O_3$

46 grating layer was treated as a homogeneous film with a refractive index

47  $n_{G\_aver} = \sqrt{n_{Al_2O_3}^2 \times f + n_{air}^2 \times (1-f)}$ . The effective refractive index of the GMR

48 grating equals to that of the  $n_{G\_aver}/ITO/Al_2O_3/ITO$  four-layer system and was

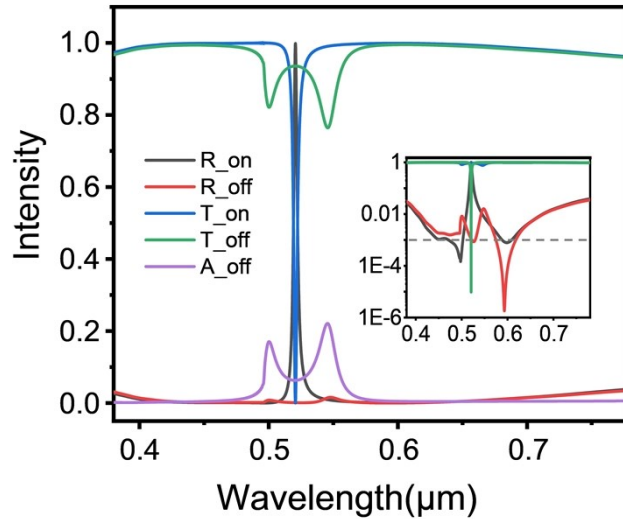
49 calculated by FDTD method.

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51 **4 Reflectance, transmittance and absorptance spectra of the green pixel at color-**  
 52 **on/off state.**

53 The reflectance near the resonance wavelength changed at least two orders and the

54 transmittance changed about five orders between color-on and color-off state.



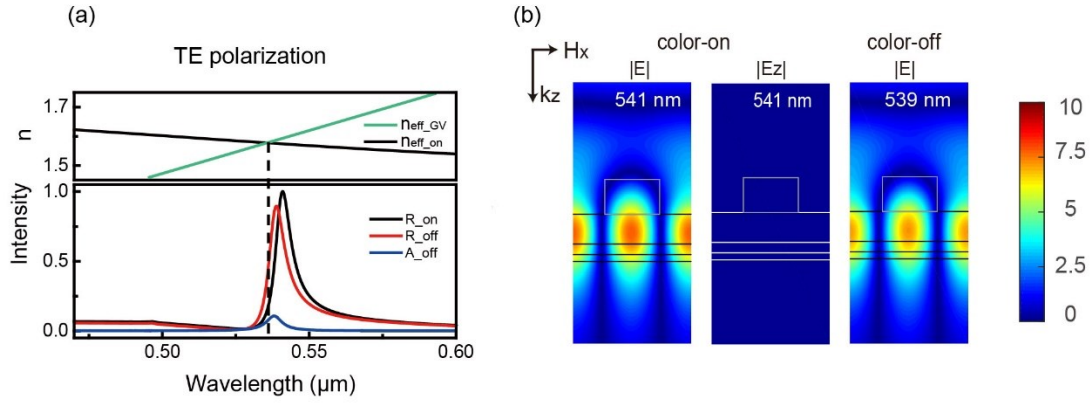
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56 **Fig. S4** The Reflectance, transmittance and absorbance spectra for the green pixel at  
 57 color-on/off state. The inset shows the transmittance and reflectance spectra in the  
 58 logarithmic scale. The structure parameters are in Table 1 in the main text.

59

## 60 **5 The GMR grating response under TE polarized light**

61 The reflectance spectra of the GMR grating at the color-on/off state under TE  
 62 polarization were plotted in Fig. S5(a). The modulation effect was much weaker than  
 63 that under TM polarization. At color-on state, the reflection peak is at 541 nm, and at  
 64 color-off state, the reflection peak moves to 539 nm. The reflection peak position is  
 65 explained by the effective mode index theory.<sup>4</sup> The reflection peaks were predicted by  
 66 the intersections between the effective index of the films  $n_{eff\_on}$  and  $n_{eff\_GV}$ . The weak  
 67 modulation effect was explained in the main text from the electric field distribution  
 68 analysis. The vertical electric field component is almost zero. So the ENZ material-  
 69 induced funneling effect was weak, and the reflectance was less affected. The slightly  
 70 reduced reflection at color-off state was due to the increased optical loss in the ITO<sub>active</sub>  
 71 layer as it changed from lossless material to lossy material.

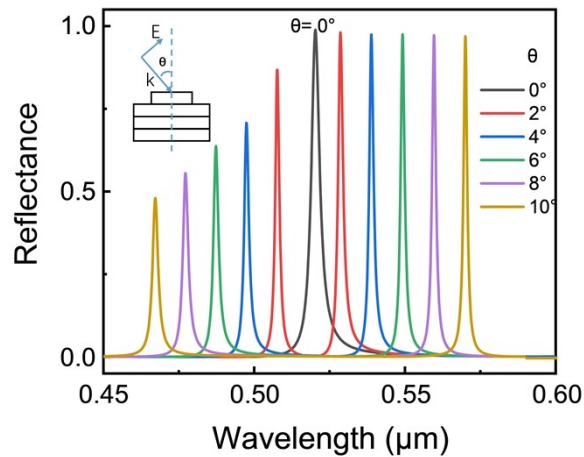


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73 **Fig. S5** (a) Up panel: The wavelength-dependent effective refractive index of the  
 74 grating vector  $n_{eff\_GV}$  (green line) and the GMR grating  $n_{eff\_on}$  (black line).  $n_{eff\_off}$   
 75 was not shown as it was almost the same as  $n_{eff\_on}$ . Bottom panel: the reflectance  
 76 spectrum at color-on state (black line), the reflectance and absorptance spectra at color-  
 77 off state (red and blue line). (b) The electric field distributions of  $|E|$  or  $|E_z|$  in the cross-  
 78 section of the GMR grating at the reflectance peak wavelength at color-on or color-off  
 79 state.

80 **6 The incident angle-dependent reflectance spectra under TM polarization.**

81 The reflectance spectra are sensitive to the incident angle.

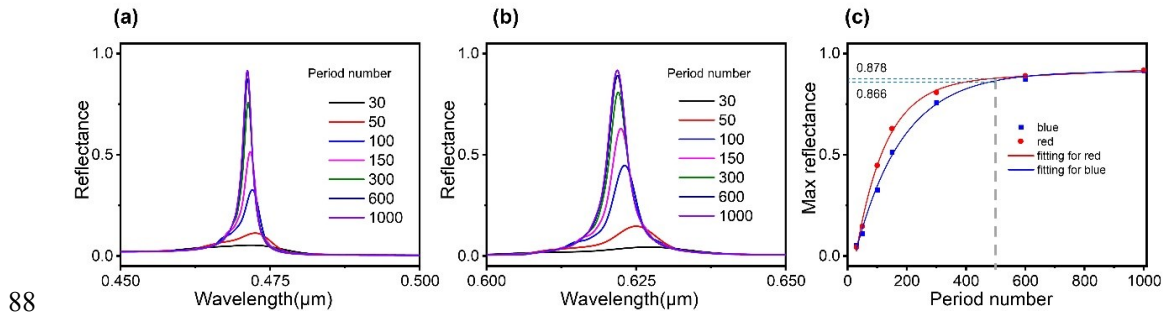


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83 **Fig. S6** The reflectance spectra for different incident angles under TM polarization for  
 84 the green pixel. The structure parameters are in Table 1 in the main text.

85

86 **7 The reflectance spectra of the red and blue pixel with different grating period**  
87 **numbers at color-on state**



88

89 **Fig. S7** The reflectance spectra with different period numbers for blue (a) or red (b)  
90 pixel. (c) The maximum reflectance dependence on the grating period numbers for blue  
91 or red pixels. The structure parameters are in Table 1 in the main text.

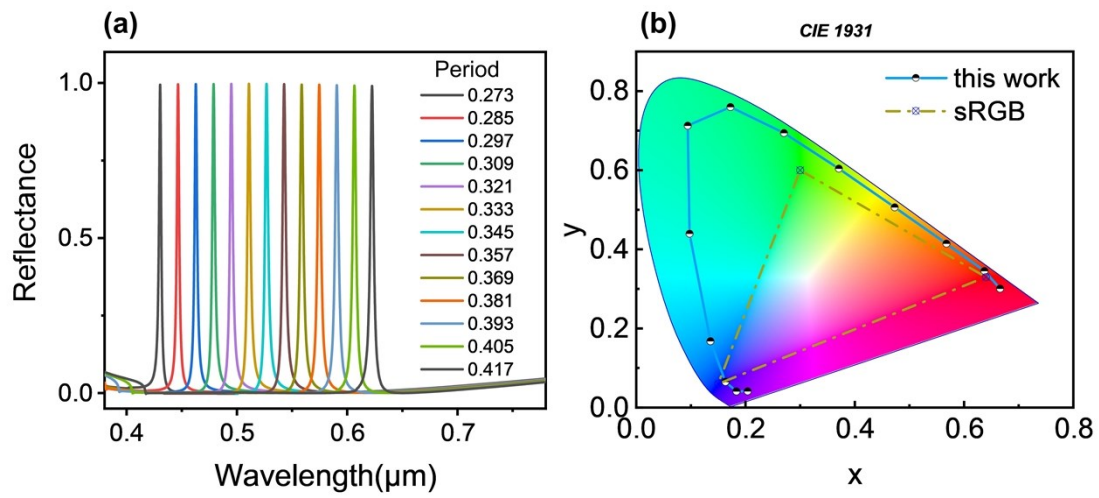
92 The display performances for red, green, and blue pixels with fixed grating period  
93 number  $N_p = 500$  are summarized as Table S1. The structure parameters are in Table 1  
94 in the main text.

95 **Table S1** The display performances for red, green, and blue pixels with fixed  
96 **grating period**  $N_p = 500$ .

	Peak intensity	Operation speed (MHz)	DPI
Red	87.8%	13.4	86
Green	90%	20.1	105
Blue	86.6%	25.6	119

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98 **8 Realization of RGB primary colors by purely changing GMR grating period**



99

100 **Fig. S8.** (a) The reflectance spectra for different grating periods. (b) The corresponding  
101 color gamut in CIE 1931 coordinates. The other geometric parameters are taken from  
102 the green pixel in Table 1 in the main text.

103

104 **Table S2.** The display performance of the green pixel with different period numbers.

$N_p$	Peak intensity	Color gamut	operation speed	DPI
(Period number)		[in unit of sRGB area]	[MHz]	
30	9.16%	77%	3712	1435
50	23.7%	113%	1336	861
90	50%	133%	412	478
100	56.4%	140%	334	430
113	60%	142%	262	381
150	71%	148%	148	287
300	84.4%	155%	37.1	143
500	90%	157%	13.4	86
600	91.7%	158%	9.28	71
1000	94.6%	159%	3.34	43
$\infty$	99.7%	161%	--	--

105 **References**

- 106 1. E. Feigenbaum, K. Diest and H. A. Atwater. Unity-order index change in transparent conducting  
107 oxides at visible frequencies, *Nano Lett*, 2010, **10**, 2111-2116.
- 108 2. J. Park, J. H. Kang, X. Liu and M. L. Brongersma. Electrically Tunable Epsilon-Near-Zero (ENZ)  
109 Metafilm Absorbers, *Sci. Rep.*, 2015, **5**, 15754.
- 110 3. Y.-W. Huang, H. W. H. Lee, R. Sokhoyan, R. A. Pala, K. Thyagarajan, S. Han, D. P. Tsai and H. A.  
111 Atwater. Gate-Tunable Conducting Oxide Metasurfaces, *Nano Lett.*, 2016, **16**, 5319-5325.
- 112 4. S. S. Wang and R. Magnusson. THEORY AND APPLICATIONS OF GUIDED-MODE  
113 RESONANCE FILTERS, *Appl. Opt.*, 1993, **32**, 2606-2613.
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